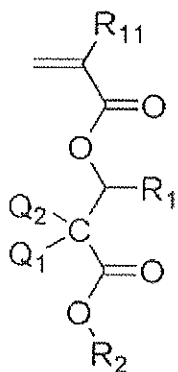


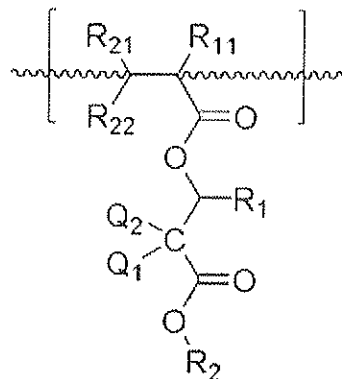
COMPOUND, COPOLYMER COMPRISING THE COMPOUND, AND RESIST
PROTECTIVE FILM COMPOSITION COMPRISING THE COPOLYMER
ABSTRACT

Provided are a compound represented by the following formula (1), a copolymer
5 including a repeating unit represented by the following formula (1-a), and a resist
protective film composition containing the copolymer. When the resist protective film
composition is used, there is obtained a resist protective film which has sufficient light
transmissivity, is not easily intermixed with the resist film, has appropriate hydrophilic or
hydrophobic characteristics, exhibits no phenomenon of pattern shape deterioration, is
10 easily dissolved in alkali developer solutions, and can reduce the occurrence of various
defects in the process of immersion or dry exposure.

[Formula 1]



[Formula 1-a]



wherein in the formula (1) and the formula (1-a), R_{11} , R_{21} and R_{22} each independently
15 represent a hydrogen atom, a halogen atom, or the like; R_1 represents an alkyl group, a
heteroalkyl group, or the like; R_2 represents a hydrogen atom or an alkyl group; and Q_1
and Q_2 each independently represent any one selected from the group consisting of a
hydrogen atom and a halogen atom.